

ABSTRACT OF THE DISCLOSURE

A lithography system for forming geometric patterns on a workpiece is described herein. The lithography system may include a reflective liquid crystal display comprising an array of configurable pixels, a radiation source for directing radiation onto the reflective liquid crystal display, a projection system for reducing a radiation pattern reflected by the reflective liquid crystal display and projecting the reduced radiation pattern onto a workpiece, and a stage for holding the workpiece. The lithography system may be used to form geometric patterns on a substrate during semiconductor fabrication.